

ATMOSPHERIC PRESSURE PLASMA MICROWAVE PROCESSING

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In 1998, Dana Corporation discovered a novel method for producing and maintaining plasma at atmospheric pressure using microwaves. Since the initial discovery of creating and controlling very high-density plasma, many new processes have evolved that were not possible before. For example, heat treating, coatings, PM sintering, surface engineering, generation of Nanotubes and other structures plus treatment of exhaust gases. In some cases concurrent processing can be accomplished. The new discovery allows existing processes such as CVD & PVD processes to occur at atmospheric pressure, that is, no expensive vacuum chamber equipment is required.